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## (54) PROTECTING MEMBER FOR INNER WALL OF CHAMBER AND PLASMA PROCESSOR

## (57)Abstract:

**PROBLEM TO BE SOLVED:** To provide a protecting member for the inner wall of the chamber of a plasma processor, which can be used for a long time by specifying the material property of glass-like carbon material and the plasma processor, wherein the described protecting member is arranged.

**SOLUTION:** A chamber inner-wall protecting member 2 is a hollow-shaped protecting member, which protects the inner wall of the chamber of a plasma processor, and is formed of the glass-like carbon material having the characteristics of the volume resistivity of  $1 \times 10^{-2} \Omega \cdot \text{cm}$  or less and a thermal conductivity of 5 W/m.K or more as an integral body structure. It is preferable that the thickness of the protecting member 2 be 4 mm or more, and the average roughness (Ra) of the inside surface of 2.0  $\mu\text{m}$  or less. The plasma processor is so constituted that the chamber inner-wall protecting member 2 having these material properties is arranged along the chamber inner-wall part of the plasma processor, the chamber inner-wall part and the protecting member 2 are conducted electrically, and the chamber is grounded.

